

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (currently amended): A method for producing a photoresist master for an optical information medium comprising the steps of:

applying a coating solution including a co-initiator and a thermally crosslinkable compound on a substrate, the co-initiator including an aliphatic or an aromatic amine;

forming a light absorbing layer comprising a co-initiator and on [[a]] the substrate by heating and curing the applied coating solution;

applying forming a photoresist layer on said light absorbing layer;

exposing the photoresist layer to a laser beam to form a latent image in the photoresist layer; and

developing the latent image to form a protrusion/depression pattern to thereby produce the photoresist master,

wherein the light absorbing layer absorbs light at the wavelength of said laser beam during said exposing step.

Claim 2 (currently amended): The method according to claim 1 wherein ~~said light absorbing layer contains an organic compound which exhibits light absorption at the wavelength of said laser beam~~ the co-initiator includes at least one of 4,4'-bis (dimethylamino) benzophenone, 4,4'-bis (diethylamino) benzophenone, ethyl 4-dimethylaminobenzoate, (n-butoxy) ethyl 4-dimethylaminobenzoate, isoamyl 4-dimethylaminobenzoate, and 2-ethylhexyl 4-dimethylaminobenzoate.

Claim 3 (canceled)

Claim 4 (original): The method according to claim 1 wherein the relation:

$$tR / \lambda E \leq 0.6$$

is satisfied when said laser beam has a wavelength of λE (unit: nm), and said photoresist layer has a thickness of tR (unit: nm).

Claim 5 (original): The method according to claim 1 wherein the relation:

$$WP / \lambda E \leq 0.9$$

is satisfied when said laser beam has a wavelength of λE (unit: nm), and said protrusion/depression pattern formed in the photoresist layer has a minimum width of WP (unit: nm).

Claim 6 (original): A method for producing a stamper for an optical information medium by using the photoresist master for an optical information medium produced by the method of claim 1, wherein said method comprises the step of transcribing said protrusion/depression pattern formed in the photoresist layer to a metal film.

Claim 7 (previously presented): The method according to claim 6 comprising the steps of:

forming a nickel thin film on said protrusion/depression pattern formed in the photoresist layer by electroless plating;

forming an electroformed film on said nickel thin film; and

peeling said metal film comprising said nickel thin film and said electroformed film to thereby produce the metal film having the protrusion/depression pattern transcribed thereto.

Claim 8 (previously presented): The method according to claim 1, wherein said light absorbing layer further comprises a dye.

Claim 9 (previously presented): The method according to claim 1, wherein said light absorbing layer further comprises a photoinitiator.

Claim 10 (previously presented): The method according to claim 1, wherein said light absorbing layer further comprises a photoinitiator and a dye.